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RASIRC
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RASIRC to Present Data of HZO Films Grown with Hydrogen Peroxide Gas

Key development in enables next generation high-K dielectric films for high volume manufacturing

San Diego, Calif – April 20, 2022 – RASIRC announced that it will be presenting "*Hydrogen Peroxide Gas: From R&D to HVM*" at the 7th Annual CMC Conference. The presentation will discuss the development of two technologies for hydrogen peroxide gas delivery that have crossed the chasm to high volume manufacturing.

"New oxidants are needed to address shrinking device size and continuously increasing three dimensional structures for NAND and DRAM," said RASIRC Founder and CEO Jeffrey Spiegelman. "These oxidants must overcome line of sight limitations of plasma, temperature limits of water and oxygen, and film damage associated with Ozone."

Device shrinkage, three dimensional and HAR structures, and lower thermal budgets all drive the continued search for new materials. A byproduct of this search is a need for better oxidants for atomic layer deposition and other thin film processes. New oxidants could help address low temperature thermal applications and simplify precursor design and selection.

Two different RASIRC technologies for Hydrogen Peroxide Gas delivery have crossed the chasm to enter HVM. Electrical data on Al2O3, HZO, and TiO2 ALD films will be presented demonstrating why hydrogen peroxide gas is expected to join the ranks of H2O and Ozone for thin film vacuum processing.

The 7th Annual CMC Conference will be held April 27-29, 2022 in Chandler, AZ at the Crowne Plaza Resort Phoenix.

About RASIRC

RASIRC transforms liquids into dynamic gases that power process innovation in semiconductor and adjacent markets. By commercializing molecules for lower temperature processes, RASIRC patented technology enables the manufacture of atomic-scale oxides, nitrides, and metals. Innovative products such as BRUTE

Peroxide, BRUTE Hydrazine, the Peroxidizer®, and Rainmaker® Humidification Systems are being used to develop solutions for 5G, AI, IOT, and advanced automation.

What makes RASIRC a unique industry leader is our technical expertise and commitment to solving complex industry challenges for our customers. Our team of industry experts has a proven track record of being first to market by efficiently delivering state of the art technology that reduces cost, improves quality, and dramatically improves safety. With our customers at the forefront of all we do, we continue to research, develop, and design innovative products that purify and deliver ultra-pure gas from liquids for the semiconductor and related markets. Contact RASIRC to help solve your complex problems.

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